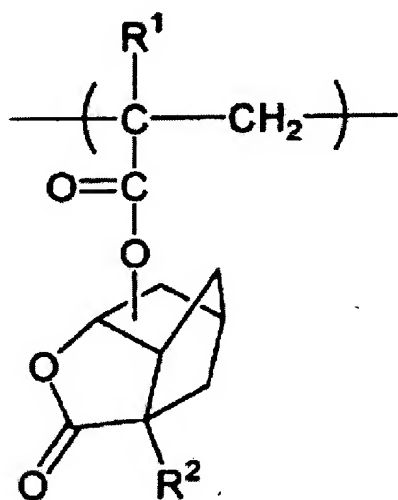


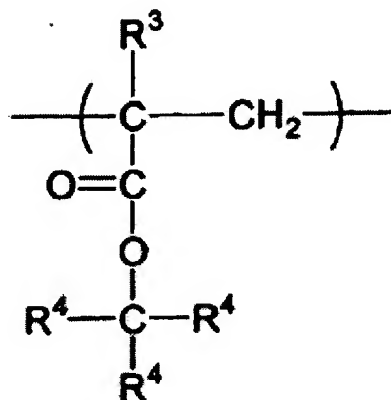
IN THE CLAIMS

1. (Original) A radiation-sensitive resin composition comprising:

(A) an acid-dissociable group-containing resin which is insoluble or scarcely soluble in alkali and becomes alkali soluble when the acid-dissociable group dissociates, the resin comprising the recurring unit of the following formula (1) and the recurring unit of the following formula (2),



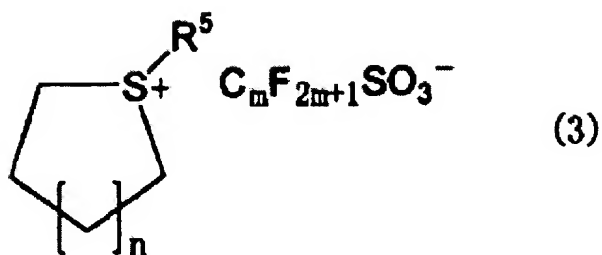
(1)



(2)

wherein R¹ and R² individually represent a hydrogen atom or methyl group, R³ represents a hydrogen atom or methyl group, and R⁴ individually represents a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, or any two of R⁴ groups form in combination a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the remaining R⁴ group being a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, and

(B) a photoacid generator of the following formula (3),



wherein R^5 represents a monovalent aromatic hydrocarbon group having 6-20 carbon atoms or a derivative thereof, m is an integer of 1-8, and n is an integer of 0-5.

2. (Original) The radiation-sensitive resin composition according to Claim 1, wherein any two of the R^4 groups in the formula (2) form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof and the remaining R^4 group is a linear or branched alkyl group having 1-4 carbon atoms.

3. (Original) The radiation-sensitive resin composition according to Claim 1, wherein R^4 in the formula (2) or the group formed by any two of the R^4 groups is an alicyclic group derived from norbornane, tricyclodecane, tetracyclododecane, or adamantane or a group in which a hydrogen atom on the aliphatic ring is replaced by an alkylene group.

4. (Original) The radiation-sensitive resin composition according to Claim 1, wherein the recurring unit of the formula (2) is a recurring unit originating from 2-methyl-2-adamantyl (meth)acrylate or 2-norbornyl-2-n-propyl (meth)acrylate.

5. (Original) The radiation-sensitive resin composition according to Claim 1, wherein the amount of the recurring unit of the formula (1) and the recurring unit of the formula (2) is respectively 10-80 mol% and 10-80 mol% of all recurring units in the resin (A).

6. (Original) The radiation-sensitive resin composition according to Claim 1, wherein R⁵ in the formula (3) is at least one group selected from the group consisting of a 3,5-dimethyl-4-hydroxyphenyl group, 4-methoxyphenyl group, 4-n-butoxyphenyl group, 2,4-dimethoxyphenyl group, 3,5-dimethoxyphenyl group, and 4-n-butoxy-1-naphthyl group.

7. (Original) The radiation-sensitive resin composition according to Claim 1, wherein m in the formula (3) is 4 or 8.

8. (Original) The radiation-sensitive resin composition according to Claim 1, wherein n in the formula (3) is 1.

9. (Original) The radiation-sensitive resin composition according to Claim 1, further comprising a photoacid generator other than the photoacid generator (B) of the formula (3).

10.(Original) The radiation-sensitive resin composition according to Claim 9, wherein the amount of the photoacid generator other than the photoacid generator (B) is 80 wt% or less of the total amount of the photoacid generators.

11.(Original) The radiation-sensitive resin composition according to Claim 1, further comprising an acid diffusion controller.

12.(Currently Amended) The radiation-sensitive resin composition according to claim [[1]] 11, wherein the acid diffusion controller is a nitrogen-containing organic compound.

13.(Original) The radiation-sensitive resin composition according to Claim 1, further comprising an alicyclic additive having an acid-dissociable group.

14.(Original) The radiation-sensitive resin composition according to Claim 1, further comprising a linear or branched ketone, cyclic ketone, propylene glycol monoalkyl ether acetate, alkyl 2-hydroxypropionate, or alkyl 3-alkoxypropionate as a solvent.